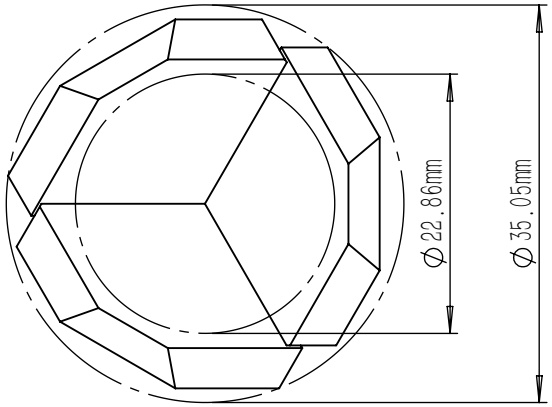
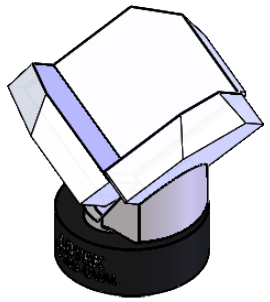
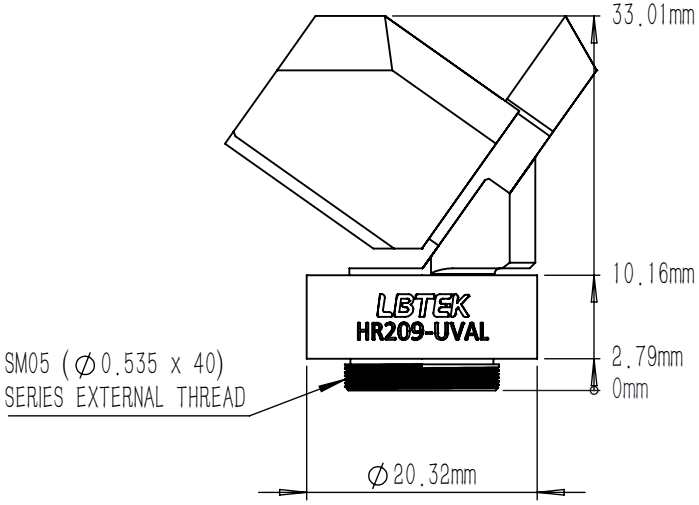
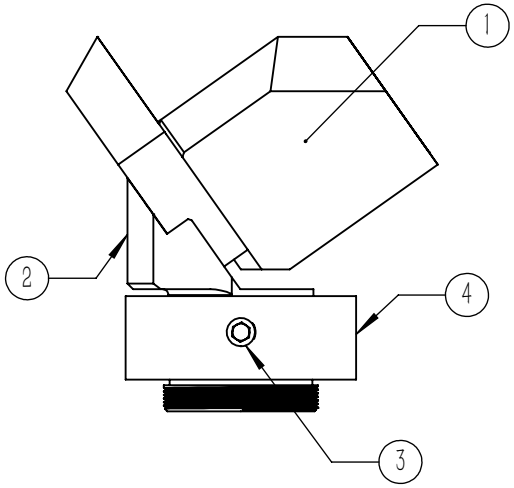
NO.	PART	MATERIAL
①	∅0.9″ HOLLOW RETROREFLECTOR MIRROR PROTECTED UV-ENHANCED ALUMINUM	UVFS
②	RETROREFLECTOR MOUNT	STAINLESS STEEL
③	M3 HEX SOCKET LOCKING SCREWS WITH NYLON HEADS ×1	STAINLESS STEEL
④	0.5-INCH OPTICAL COMPONENT MOUNTING ADAPTER, WITH SM05 EXTERNAL THREADS, WITH ENGRAVING	ANODIZED ALUMINUM









NOTE:

1. OPERATION WAVELENGTH: 250 nm–600 nm
2. SUBSTRATE MATERIAL: UVFS
3. Substrate THICKNESS: 5 mm
4. CLEAR APERTURE: ∅22.86 mm (∅0.9″)
5. SURFACE QUALITY: 60/40
6. SURFACE FLATNESS: <2λ@633 nm
7. BEAM DEVIATION: <20 arcsec
8. COATING: PROTECTED UV-ENHANCED ALUMINUM
   Ravg>90%@250 nm–600 nm

DRAWING PROJECTION			LBTEK			
	NAME	DATE	HR209-UVAL			
DRAWN	LTAN	Apr./10th/26	HOLLOW RETROREFLECTOR MIRROR ∅0.9″, SM05, UVAL: 250 nm–600 nm			
APPROVAL	WCHEN	Apr./10th/26	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			N/A	22 g	1.5:1	A